

# Analysis of the Leakage Current of GaInP/AlGaInP High Power Lasers with a self-consistent Simulation Model

**J. M.G. Tijero<sup>1</sup>, H. Odriozola<sup>1</sup>, I. Esquivias<sup>1</sup>, A. Martín-Mínguez<sup>1</sup>, P. Brick<sup>2</sup>, M. Reufer<sup>2</sup>, M. Bou Sanayeh<sup>2</sup>, A. Gomez-Iglesias<sup>2</sup>, and N. Linder<sup>2</sup>**

(<sup>1</sup>) E. T. S. I. Telecomunicación, Univ. Politécnica de Madrid. Madrid, Spain.

(<sup>2</sup>) Osram Opto Semiconductors, Regensburg, Germany.

Work supported by **IST** project 2005-035266 **WWW.BRIGHTER:EU**, and by **MEC** (Spain) projects TEC2006-13887 and TEC2007-29619.



Opto Semiconductors

**OSRAM**

# Outline

- Introduction and goals
- Experimental characterisation
- Simulation model
- Analysis of leakage current: sensitivity to model parameters
- Conclusions



# High Power Red Lasers

Main applications:

- Photodynamic Therapy
- Fluorescence Imaging of Cancer
- Laser Display Technology
- Pumping of Solid State Lasers

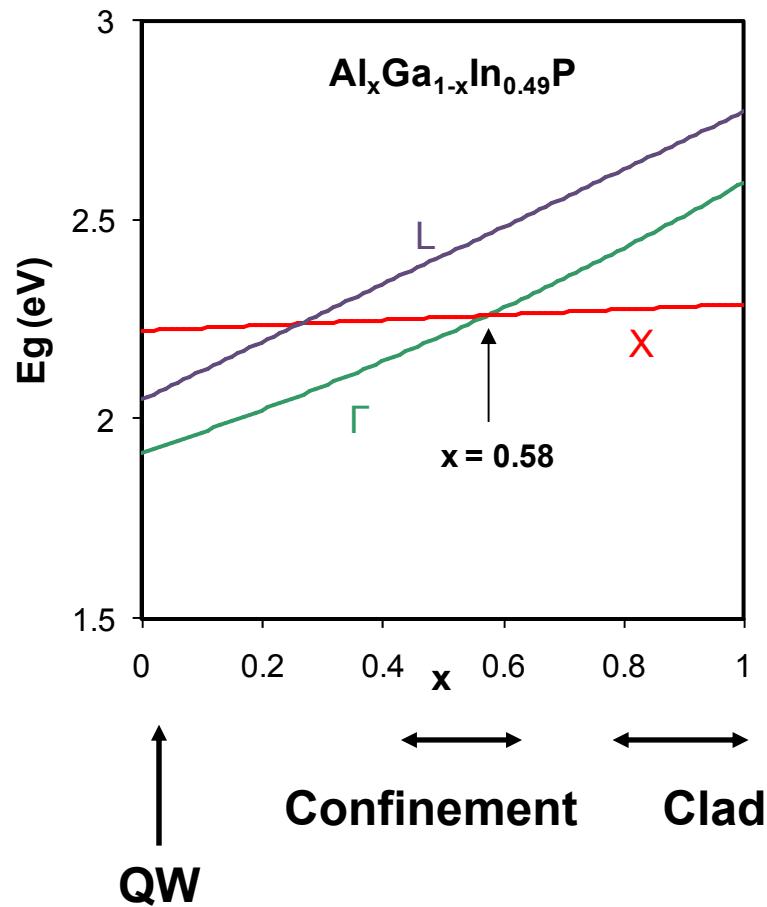
Main problems:

- High dependence of threshold current with temperature
- Decrease of slope efficiency with temperature
- Catastrophical Optical Damage
- Gradual degradation

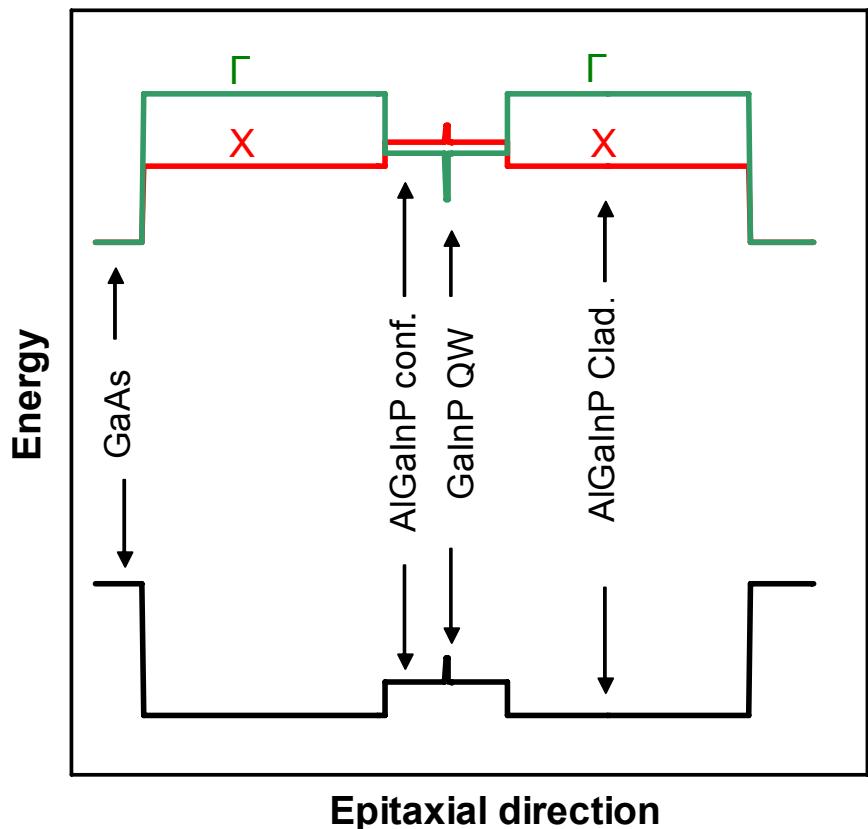


# GalnP/AlGaNp Red Lasers

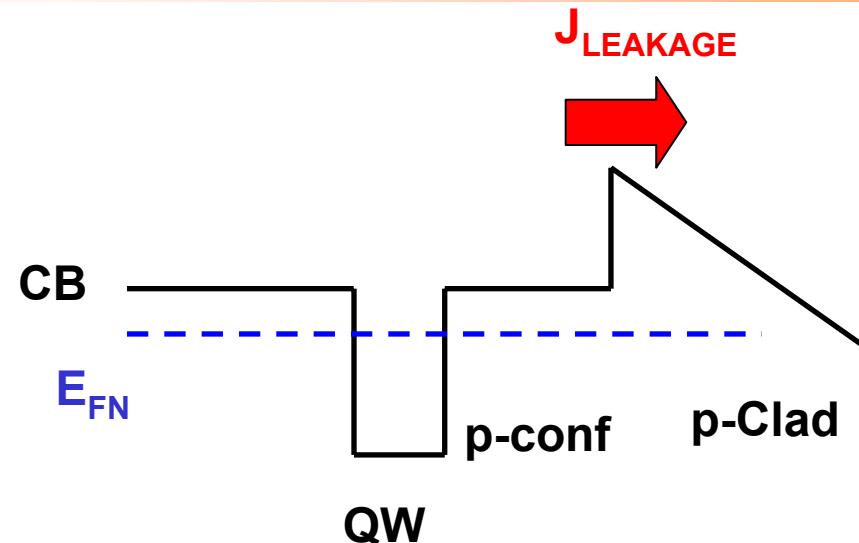
Band-gap vs. composition



Schematic band alignment



# Leakage Current in Red Lasers



## Analytical Model

$$J_{LEAK} = J_{DRIFT} + J_{DIFFUSION}$$

Leakage current depends on:  
band-offset, mobilities, carrier lifetime....



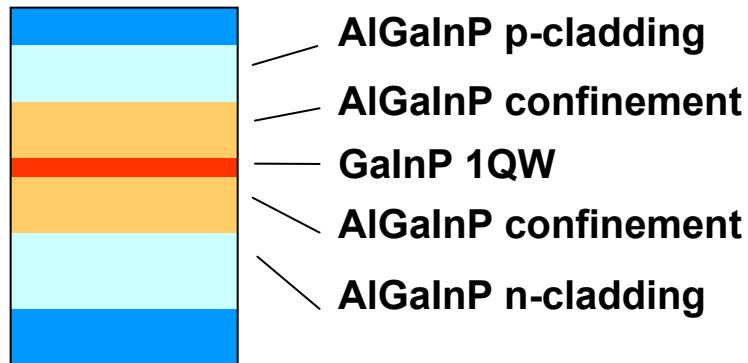
## Goals

- Analyze leakage current with a self-consistent laser model
- Evaluate the sensitivity of the results to the values of some material parameters
- Evaluate the effect of some design parameters: p-doping



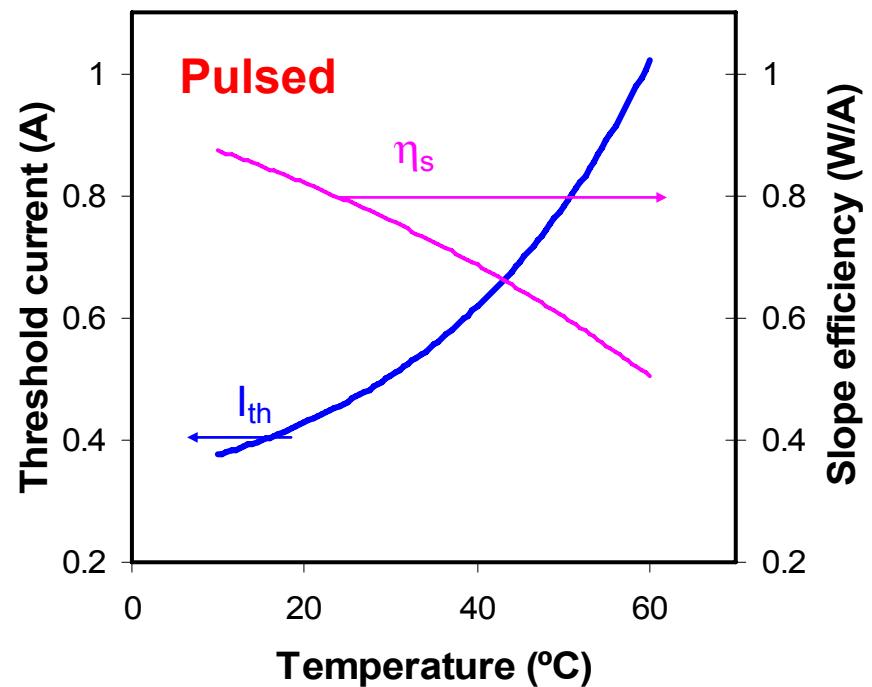
# Laser Devices and Experimental characterisation

## Epitaxial design



Wavelength: 635 nm

Broad Area Lasers  
100  $\mu\text{m} \times 1.2 \text{ mm}$



# Self-consistent laser model

## Main features:

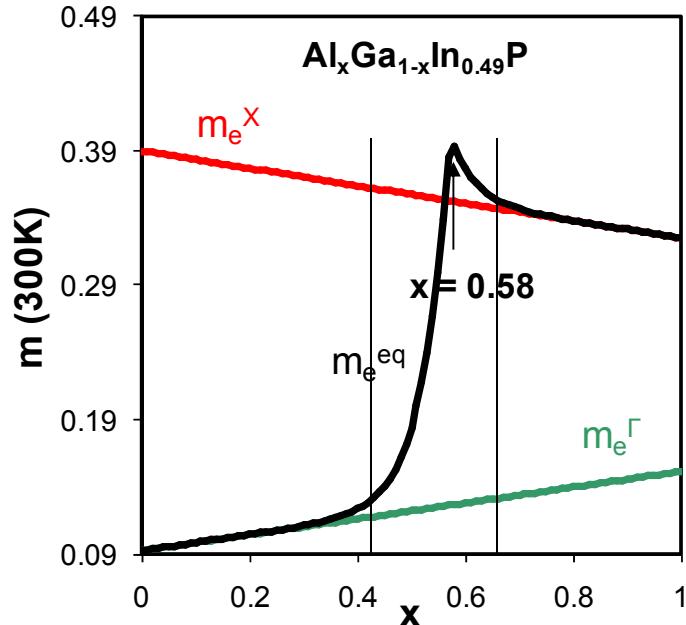
- Complete semiconductor equations: Poisson + continuity electrons + continuity holes
- QW carrier capture/escape processes
- Gain calculations using parabolic fitting of VB structure (calculated by  $k.p$  band mixing model)
- $\Gamma$  and X valleys in the CB



# Model for multiple valleys in CB

- Assumption: thermal equilibrium between electrons in different valleys
- Single CB minimum with equivalent effective mass and mobility
- $m_e^{eq}$  and  $\mu_e^{eq}$  are calculated analytically

$$m_e^{eq} = f_m(m_e^X, m_e^\Gamma, E_C^X - E_C^\Gamma, T)$$
$$\mu_n^{eq} = f_\mu(\mu_n^X, \mu_n^\Gamma, E_C^X - E_C^\Gamma, T)$$



Equivalent effective electron mass

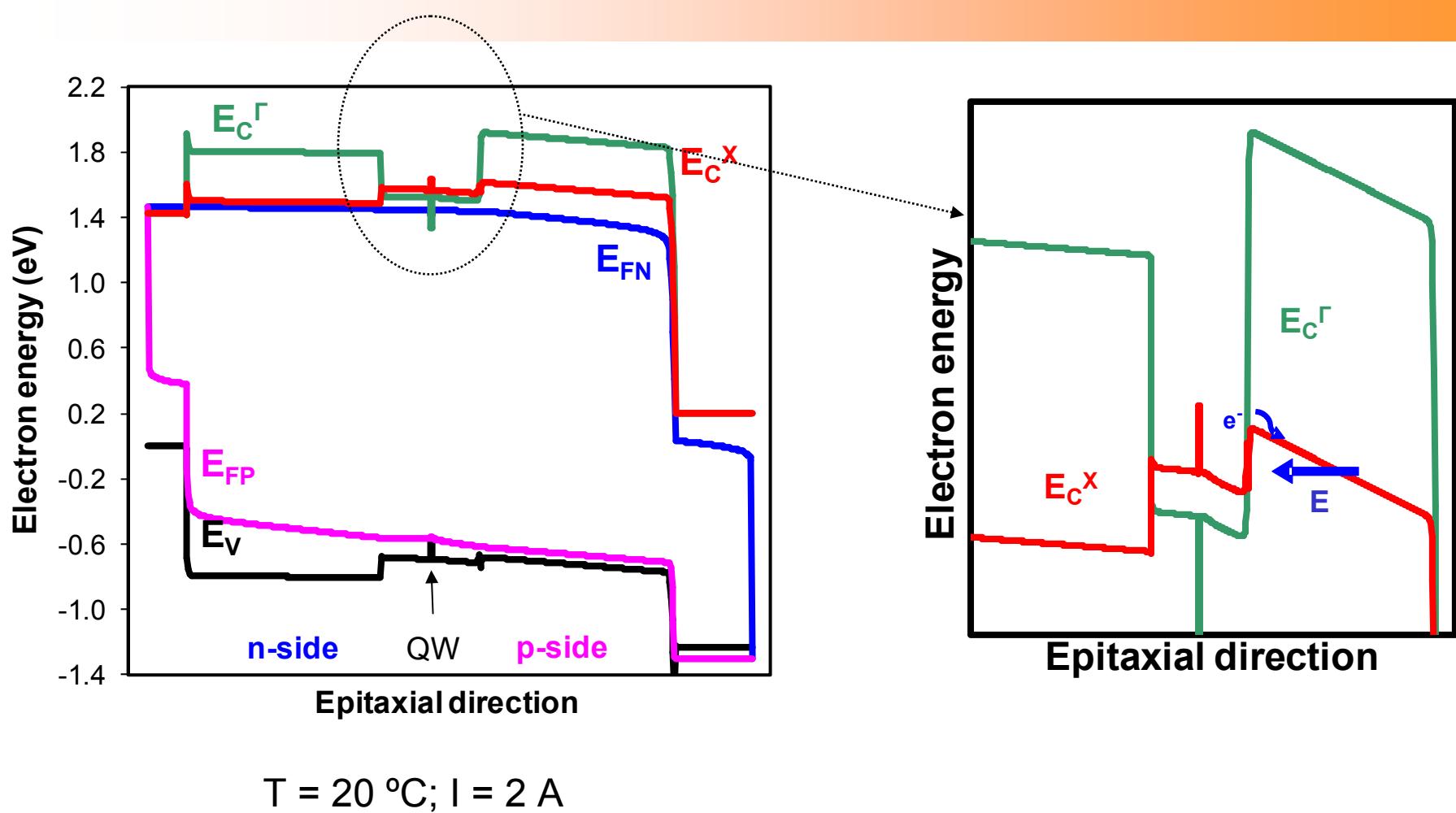


# Main model parameters affecting leakage

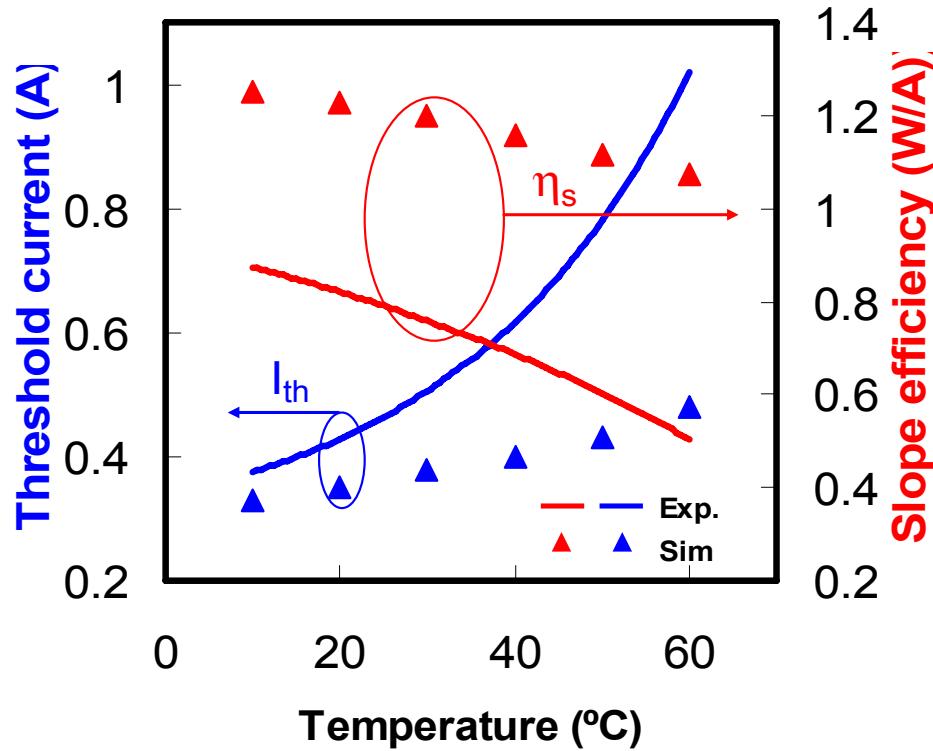
- **Electron/ hole mobilities**
- **Electron/ hole capture times**
- Band line-ups
- $\Gamma$  and X valleys effective masses
- **SRH recombination parameters:** trap density, trap energy, trap carrier capture section



# Band profiles under bias



## No SRH recombination

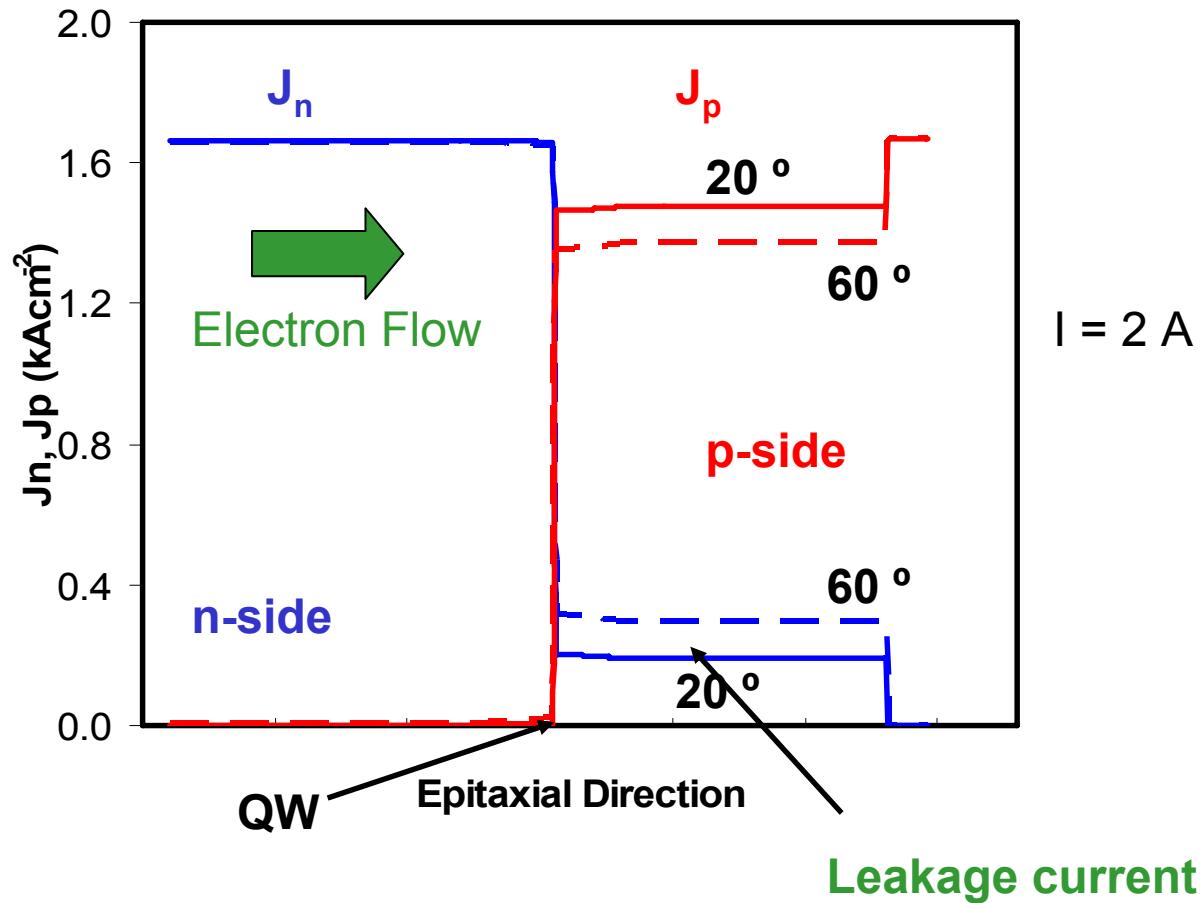


- ✓ Low  $I_{\text{th}}$ ; weak temperature dependence
- ✓ High  $\eta_s$ ; weak temperature dependence

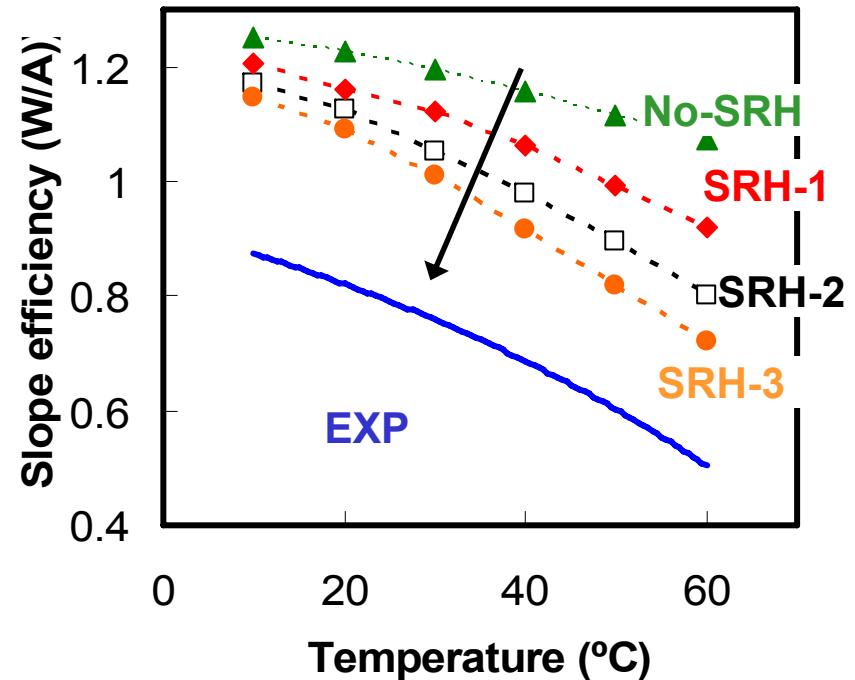
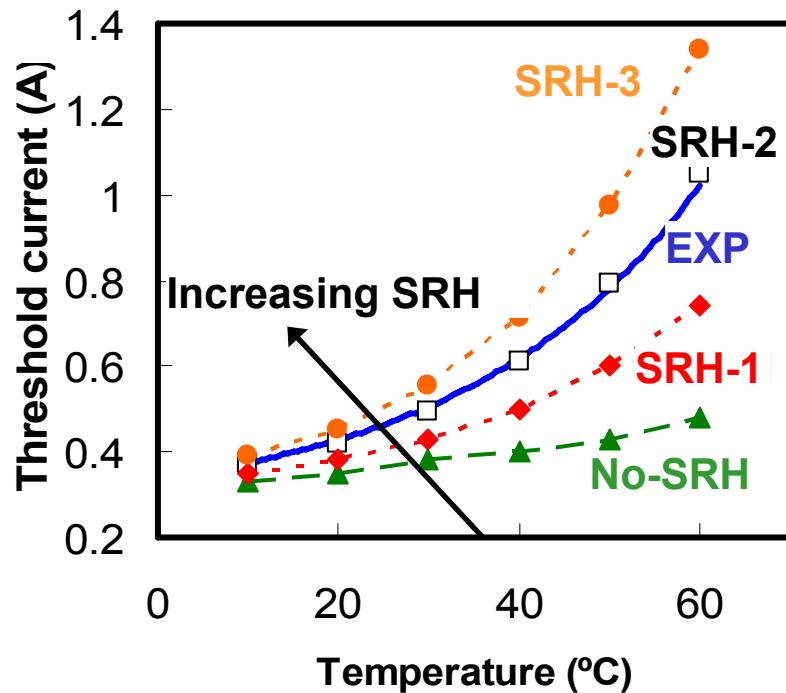


# No SRH recombination

Current density profile



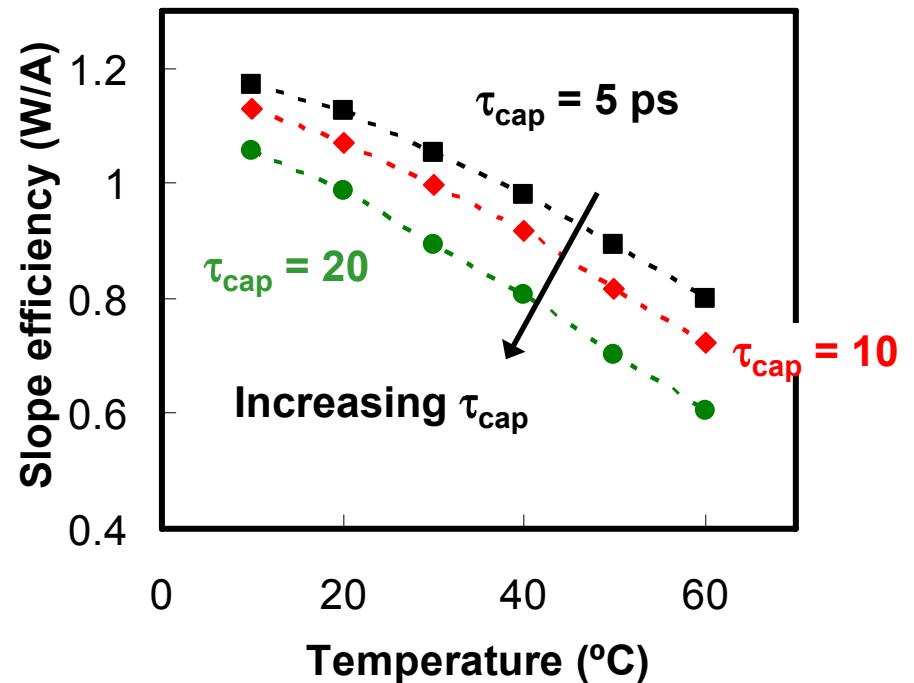
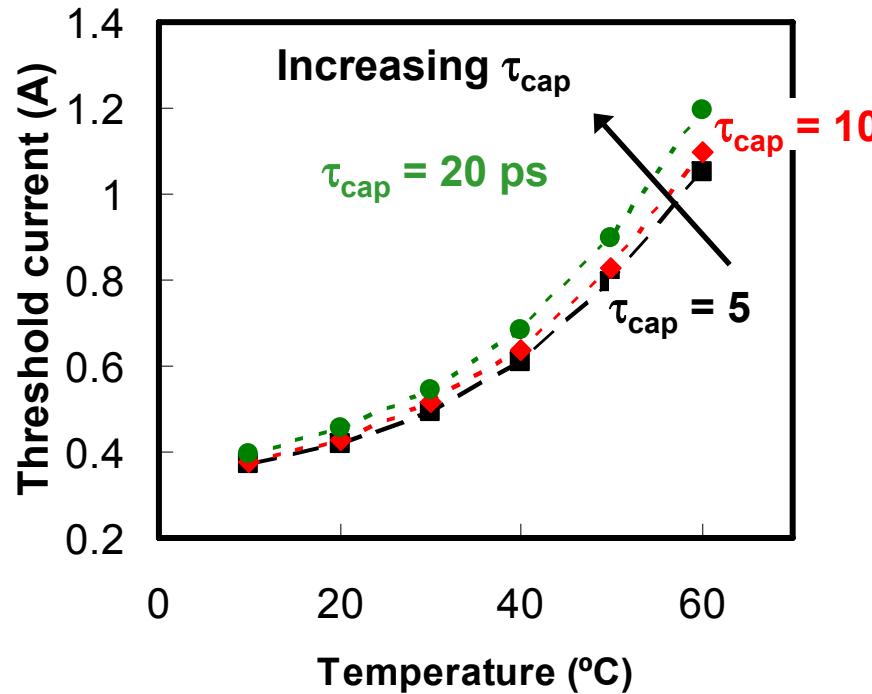
# Role of SRH recombination



	Traps in p-conf	Traps in p-clad
SRH-1	$1 \cdot 10^{17} \text{ cm}^{-3}$	$0.5 \cdot 10^{16} \text{ cm}^{-3}$
SRH-2	$3 \cdot 10^{17} \text{ cm}^{-3}$	$1 \cdot 10^{16} \text{ cm}^{-3}$
SRH-3	$5 \cdot 10^{17} \text{ cm}^{-3}$	$1.5 \cdot 10^{16} \text{ cm}^{-3}$



# Role of electron capture time



$\tau_{cap} \uparrow \rightarrow I_{leakage} \uparrow$

(Increasing electron density in confinement layers)



# Role of carrier mobility in p-clad

$$\mu_p \text{ (majority)} \uparrow \longrightarrow I_{\text{leakage}} \text{ (drift)} \downarrow$$

Lower Electric field ( $J_p = qp\mu_p E$ )

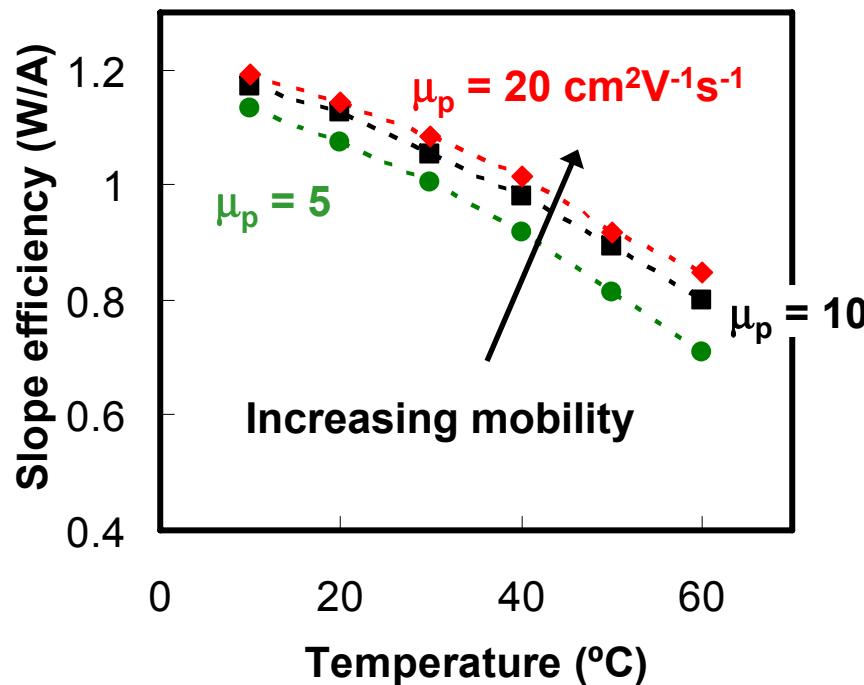
$$\mu_n \text{ (minority)} \uparrow \longrightarrow I_{\text{leakage}} \text{ (diffusion)} \uparrow$$

Higher diffusion coefficient ( $J_{n \text{ (dif)}} = \mu_n kT d_n/dx$ )

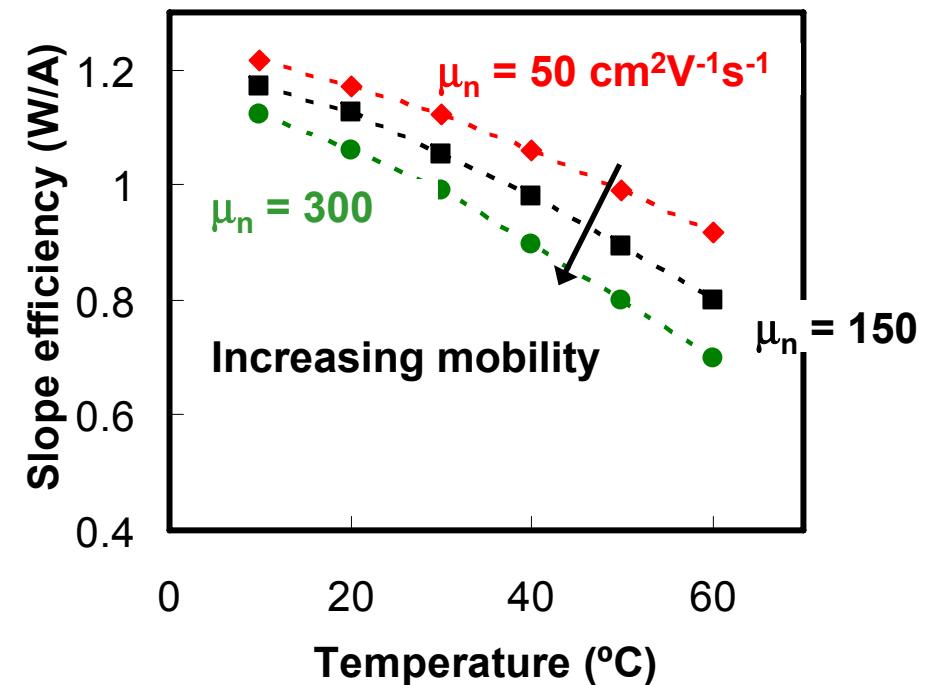


# Role of carrier mobility in p-clad

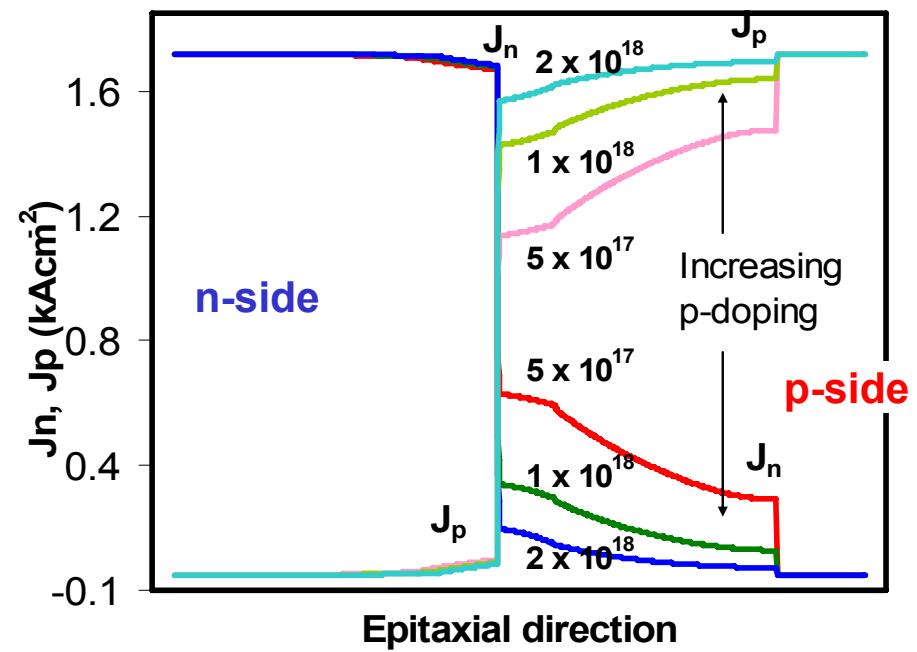
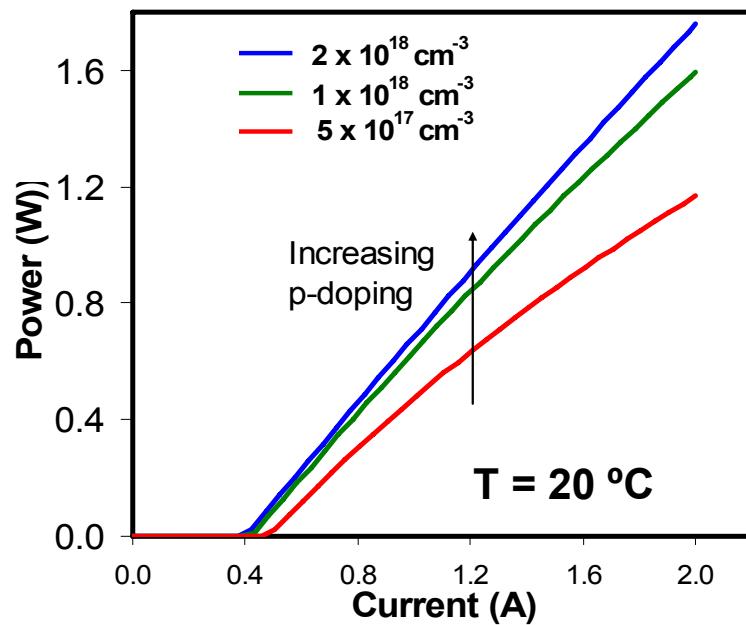
$\mu_p$  (majority)



$\mu_n$  (minority)



# Role of doping in p-cladding



$T = 20^\circ\text{C}; I = 2 \text{ A}$

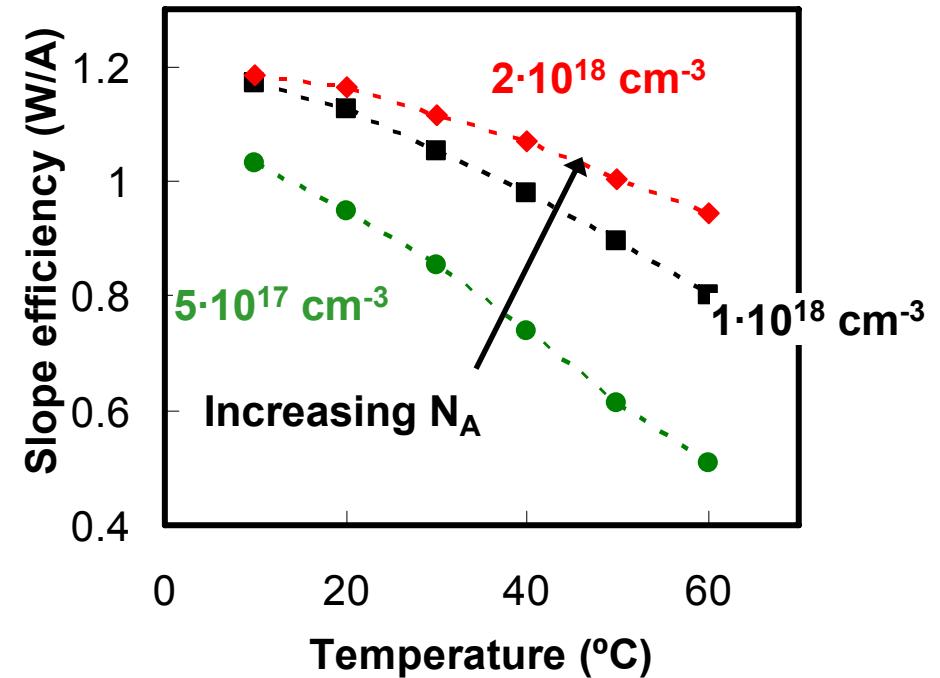
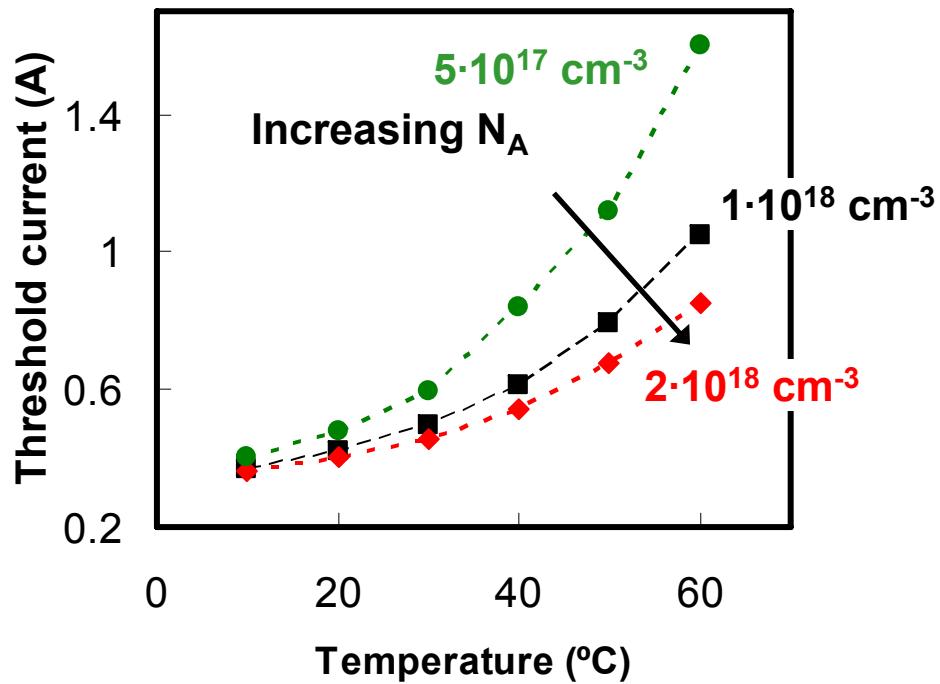


NUSOD'08 Nottingham. September 08- 18

Opto Semiconductors

18  
OSRAM

# Role of doping in p-cladding



✓ Increasing p-doping reduces drift leakage

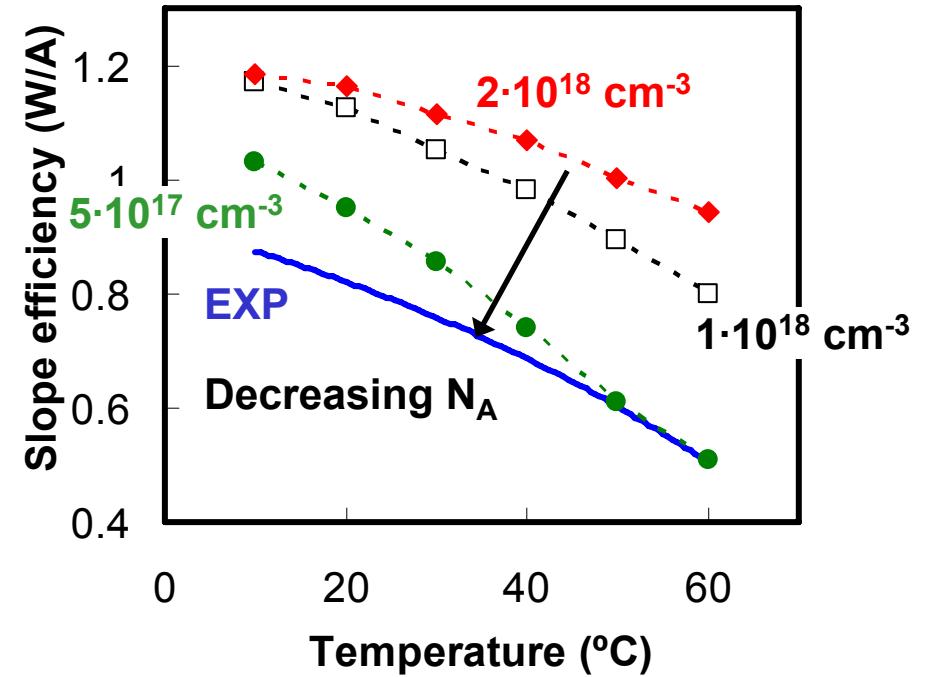
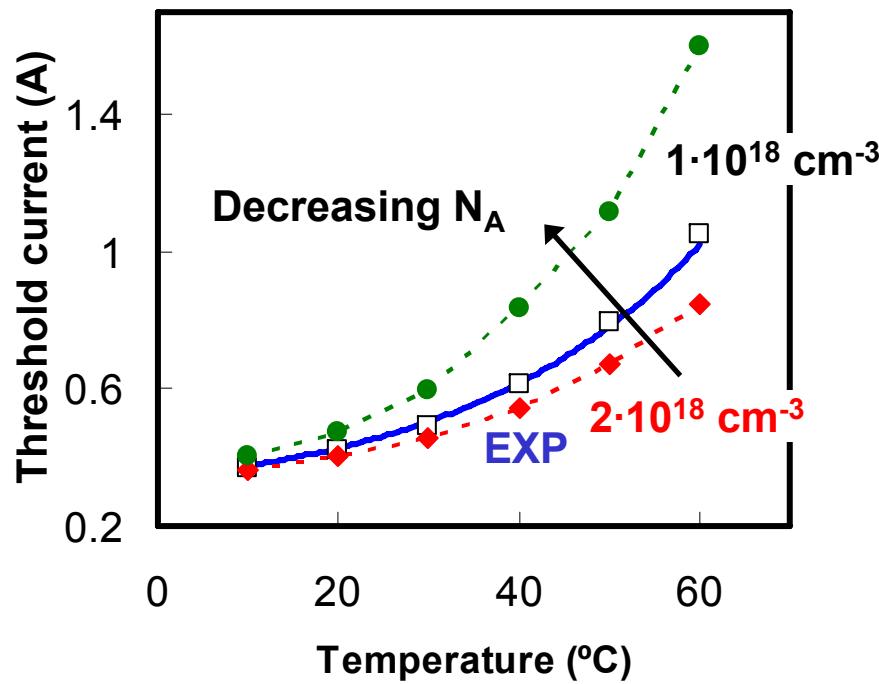


# Conclusions

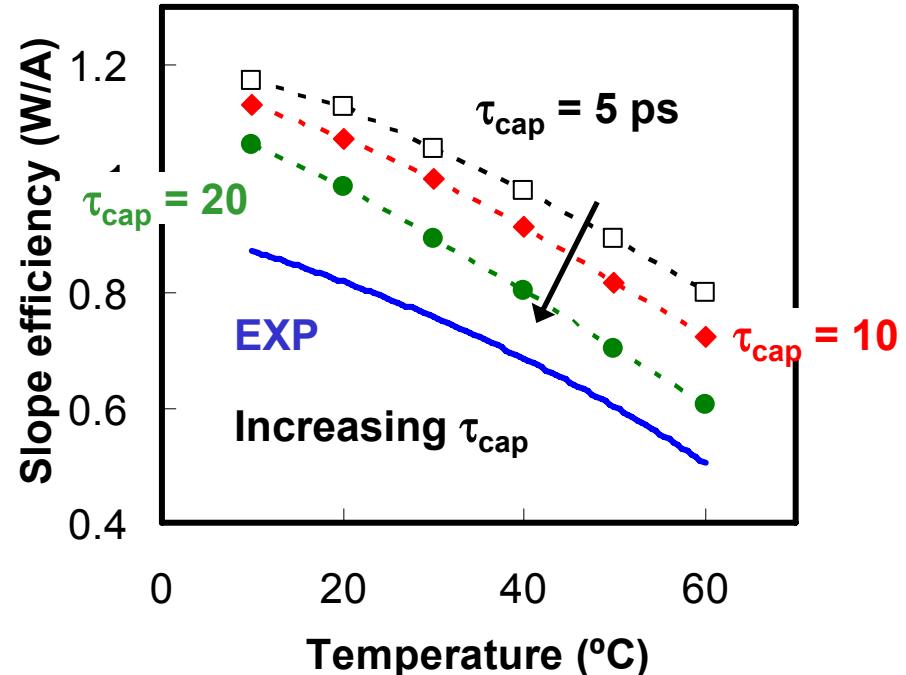
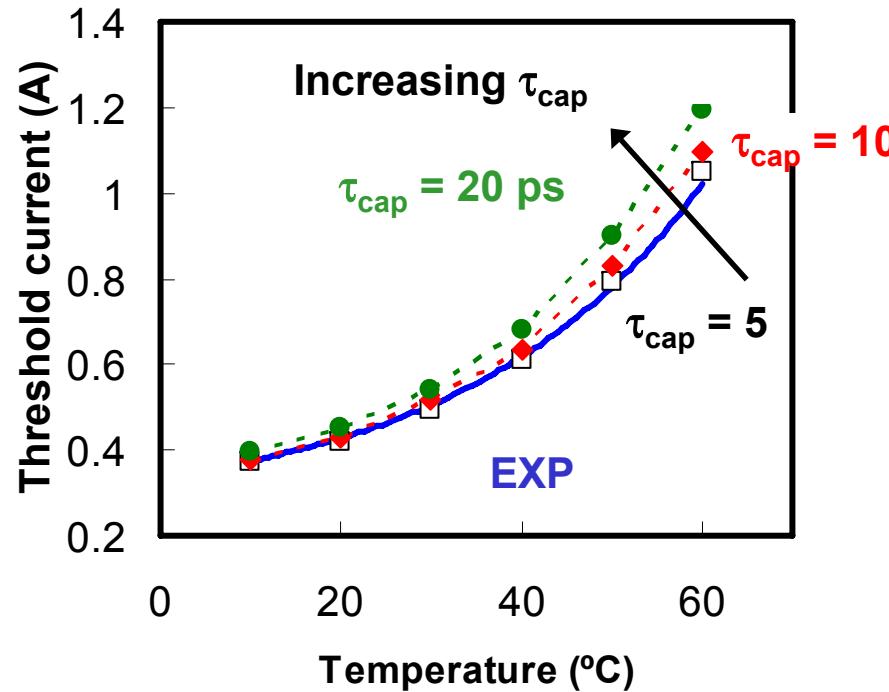
- ✓ Self-consistent model predicts leakage current over p-cladding
- ✓ Leakage current is very sensitive to model parameters
- ✓ Need to determine basic material parameters to optimize red lasers
- ✓ Simulation emphasizes the Important role of increasing p-doping level.



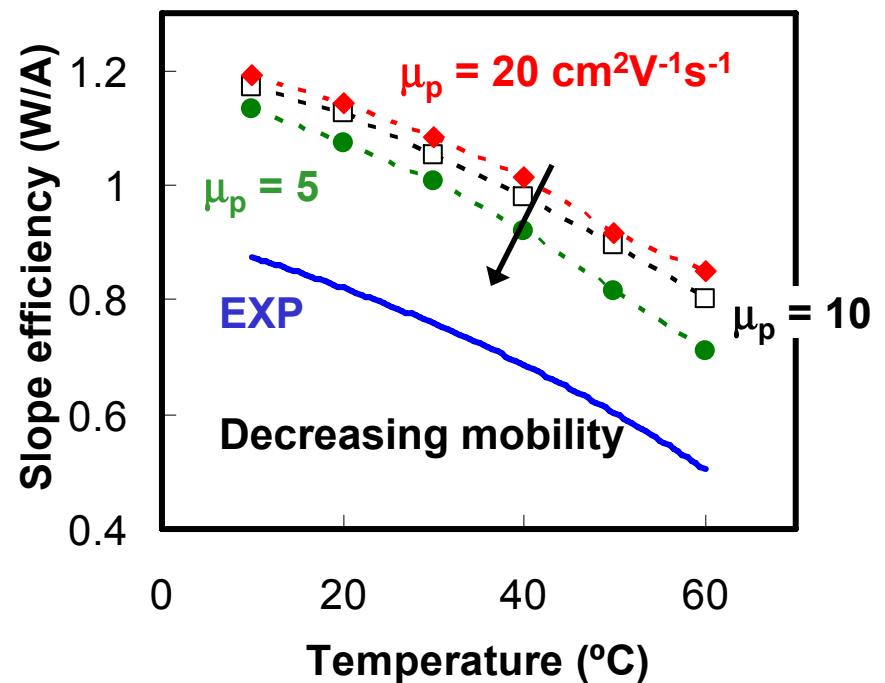
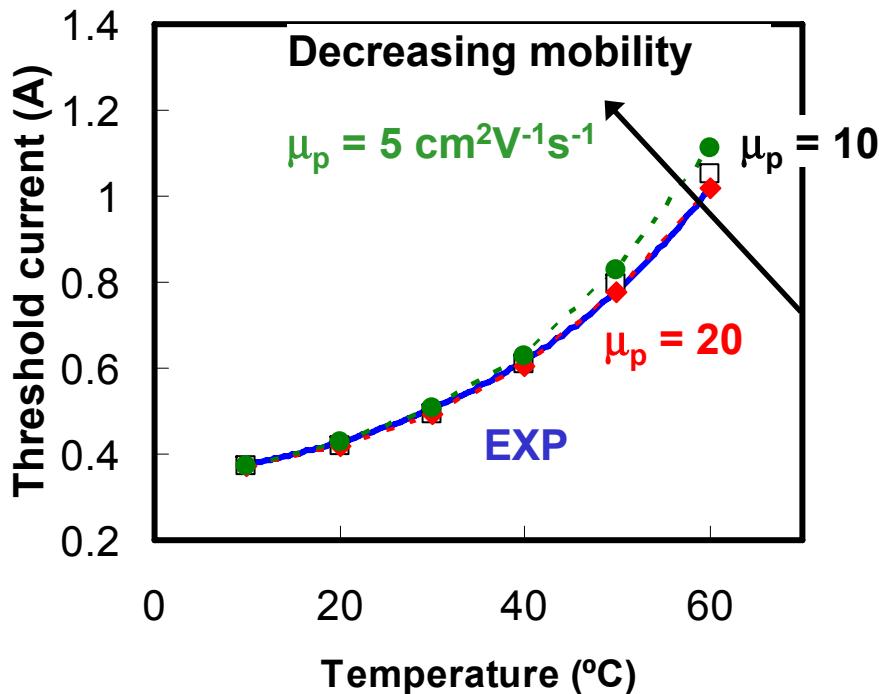
# Role of doping in p-cladding



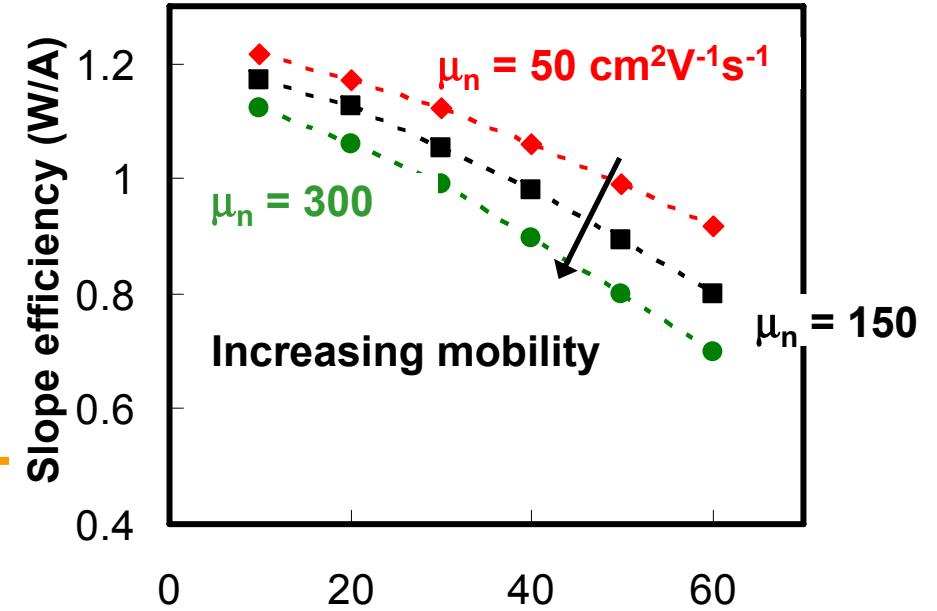
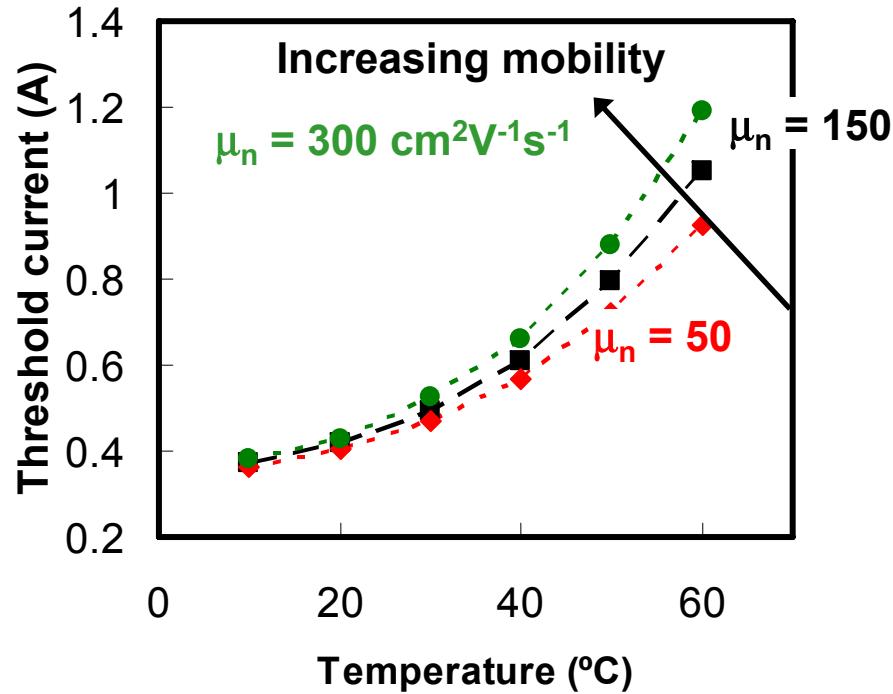
# Role of electron capture time



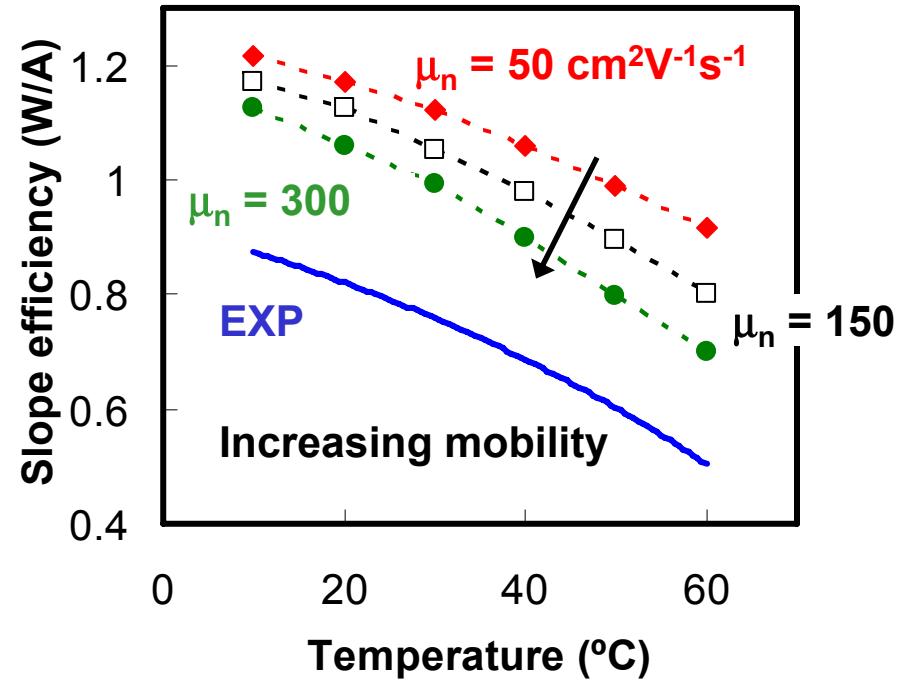
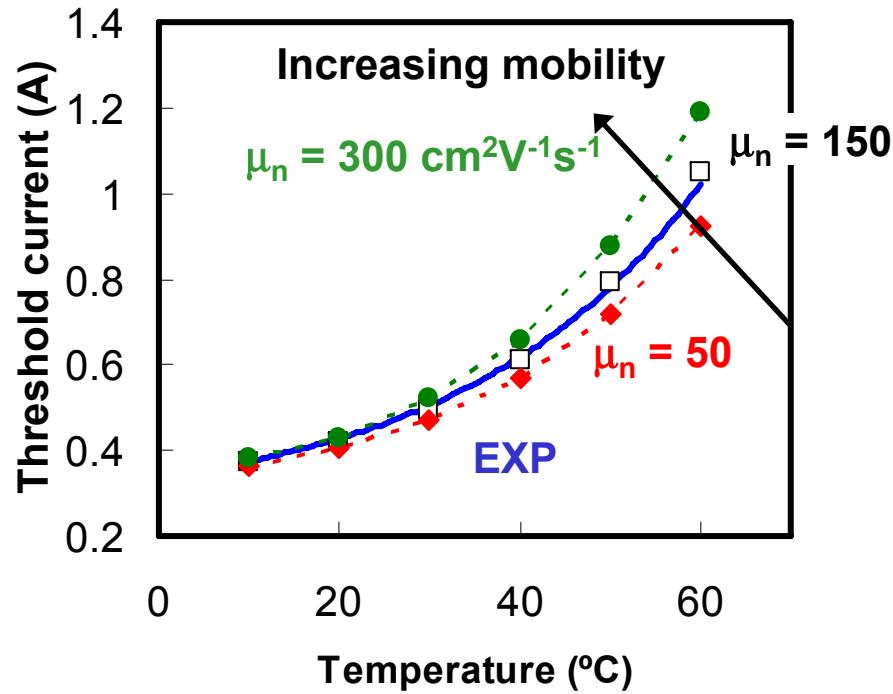
# Role of hole mobility in p-clad



# Role of electron mobility in p-clad



# Role of electron mobility in p-clad



# Role of hole mobility in p-clad

